IN THE CLAIMS:

1. (Currently Amended) A manufacturing apparatus comprising:

a loading chamber;

a transporting chamber coupled to the loading chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber;

a plurality of second film formation chambers coupled to the transporting chamber;

a first processing chamber coupled to the transporting chamber,

a second processing chamber coupled to the transporting chamber[[;]],

wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material,

wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer,

wherein each of the plurality of second film formation chambers is coupled to a vacuum pump,

wherein each of the plurality of second film formation chambers comprises:

an alignment means for performing a position alignment of a mask and a substrate;

a substrate holding means;

an evaporation source holder; and

a means for moving the evaporation source holder;

wherein the evaporation source holder comprises:

a container that seals an evaporation material;

a means for heating the container; and

a shutter provided over the container;

wherein the second processing chamber is coupled to a vacuum pump,

wherein a plurality of plate heaters are disposed within the processing chamber so as to overlap with each other and have gaps therebetween, and

wherein the second processing chamber can perform a vacuum heating on a plurality of substrates, and

wherein each of substrates is held by substrate holders attached to first and second panel heaters holding the plurality of plate heaters.

2. (Previously presented) A manufacturing apparatus according to claim 1, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

3. (Previously presented) A manufacturing apparatus according to claim 2, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

4. (Original) A manufacturing apparatus according to claim 1, wherein a hole of an opening surface area S2, which is smaller than an opening surface area S1 of the container, is opened in the shutter.

5. (Previously presented) A manufacturing apparatus according to claim 1, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

6-13. (Canceled)

14. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate; [[and]]

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein each of substrates is held by substrate holders attached to first and second panel heaters holding a plurality of plate heaters.

15. (Previously presented) A manufacturing apparatus according to claim 14, wherein the evaporation source holder comprises a heater.

16. (Previously presented) A manufacturing apparatus according to claim 14, wherein the evaporation source holder comprises a shutter having a hole.

17. (Previously presented) A manufacturing apparatus according to claim 14, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

18. (Previously presented) A manufacturing apparatus according to claim 14, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

19. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a film second formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate; [[and]]

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber comprises a plurality of plate heaters held between panel heaters, and is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein a plurality of substrate holders are attached to the panel heaters, and each of substrate holders are positioned between two plate heaters.

20. (Previously presented) A manufacturing apparatus according to claim 19, wherein the evaporation source holder comprises a heater.

21. (Previously Presented) A manufacturing apparatus according to claim 19, wherein the evaporation source holder comprises a shutter having a hole.

22. (Previously presented) A manufacturing apparatus according to claim 19, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

23. (Previously presented) A manufacturing apparatus according to claim 19, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

24. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate, and a means for moving the evaporation source holder; [[and]]

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein each of substrates is held by substrate holders attached to first and second panel heaters holding a plurality of plate heaters.

25. (Previously presented) A manufacturing apparatus according to claim 24, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

26. (Previously presented) A manufacturing apparatus according to claim 25, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

27. (Previously presented) A manufacturing apparatus according to claim 24, wherein the evaporation source holder comprises a heater.

28. (Previously presented) A manufacturing apparatus according to claim 24, wherein the evaporation source holder comprises a shutter having a hole.

29. (Previously presented) A manufacturing apparatus according to claim 24, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

30. (Previously presented) A manufacturing apparatus according to claim 24, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

31. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate, and a means for moving the evaporation source holder; [[and]]

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber comprises a plurality of plate heaters held between panel heaters, and is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein a plurality of substrate holders are attached to the panel heaters, and each of substrate holders are positioned between two plate heaters.

32. (Previously presented) A manufacturing apparatus according to claim 31, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

33. (Previously presented) A manufacturing apparatus according to claim 32, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

34. (Previously presented) A manufacturing apparatus according to claim 31, wherein the evaporation source holder comprises a heater.

35. (Previously presented) A manufacturing apparatus according to claim 31, wherein the evaporation source holder comprises a shutter having a hole.

36. (Previously presented) A manufacturing apparatus according to claim 31, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

37. (Previously presented) A manufacturing apparatus according to claim 31, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

38. (Currently Amended) A manufacturing apparatus according to claim 1, wherein the plurality of substrates are heated by a [[the]] thermal radiation of an infrared light.

39. (Currently Amended) A manufacturing apparatus according to claim 14, wherein the plurality of substrates are heated by a [[the]] thermal radiation of an infrared light.

40. (Currently Amended) A manufacturing apparatus according to claim 19, wherein the plurality of substrates are heated by a [[the]] thermal radiation of an infrared light.

41. (Currently Amended) A manufacturing apparatus according to claim 24, wherein the plurality of substrates are heated by a [[the]] thermal radiation of an infrared light.

42. (Currently Amended) A manufacturing apparatus according to claim 31, wherein the plurality of substrates are heated by a [[the]] thermal radiation of an infrared light.

43. (Previously presented) A manufacturing apparatus according to claim 1, wherein the vacuum pump is at least one of a magnetic levitation turbo-molecular pump, a cryopump, and a dry pump.